

**AMENDMENTS TO THE CLAIMS**

This listing of claims replaces all prior versions of claims in the application.

Claims 1-79 (Cancelled).

Claim 80 (Previously Presented): A plural beam-type testing apparatus comprising:  
a plurality of charged particle beam sources; and  
a plural beam generator for forming a plurality of charged particle beams and including a partition wall disposed to receive said plurality of charged particle beams, said wall having a plurality of holes, each of said holes being disposed in said wall to pass the charged particle beam for a corresponding one of said beam sources, wherein each of said holes is disposed at a position offset from the irradiating axes of said corresponding one of said beam sources.

Claim 81 (Previously Presented): A plural beam-type testing apparatus according to claim 80, wherein said partition wall has a high rigidity.

Claim 82 (Previously Presented): An electron beam apparatus comprising:  
a stage for holding an object under testing;  
a beam generator for generating a charged particle beam from said beam generator as a primary beam;  
an electro-optical system for guiding said primary beam in one direction and for guiding a secondary charged particle beam generated from said object in the opposite direction;

an EXB separator for applying a magnetic field and an electric field to said secondary charged particle beam to deflect said primary or secondary charged particle beam thereby separating said secondary charged particle beam from said primary beam, wherein an amount of deflection effected by the magnetic field is equal to twice an amount of deflection effected by the electric field, and a direction of deflection effected by the magnetic field is opposite to a direction of deflection by the electric field.

Claims 83-84 (Cancelled).

Claim 85 (Previously Presented): An electron beam apparatus comprising:

an electron source comprising a first electrode applied with a voltage close to a ground and a second electrode applied with a voltage remote from the ground;

an objective lens;

a secondary electron detector,

a first controller having a mechanism for changing a focal length of said objective lens by changing a voltage applied to a said first electrode of said objective lens;

a second controller having a mechanism for changing a voltage applied to a second electrode of said objective lens to largely change the focal length of said objective lens.

Claims 86-94 (Cancelled).

Claim 95 (Previously Presented): An electron beam apparatus comprising:

a stage for holding an object under testing;

a beam generator for generating a primary charged particle beam;

an electro-optical system for guiding said primary beam in one direction and for guiding a secondary charged particle beam generated from said object in the opposite direction;

an EXB separator for applying a magnetic field and an electric field to said primary and said secondary charged particle beam to deflect said primary and said secondary charged particle beam thereby separating said secondary charged particle beam from said primary beam; wherein,

a deflection angle for said primary beam or said secondary beam is about 3 times as large as the deflection angle for said secondary beam or said primary beam, respectively.

Claim 96 (Previously Presented): An electron beam apparatus according to claim 85, wherein said first controller has a mechanism for changing a voltage applied to a third electrode of said objective lens to change the focal length of said objective lens with high speed.

Claim 97 (Previously Presented): An electron beam apparatus according to claim 85, further comprising a third controller having a mechanism for changing a voltage applied to a third electrode of said objective lens to change the focal length of said objective lens with high speed.